



PATENT
2658-0250P

IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Il Ryong PARK Conf.: 6588
Appl. No.: 09/740,830 Group: 1763
Filed: December 21, 2000 Examiner: A. Crowell
For: ETCH/STRIP APPARATUS INTEGRATED WITH
CLEANING EQUIPMENT

#7A
9/4/02
MW

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TC 1700

REPLY UNDER 37 C.F.R. § 1.111

Assistant Commissioner for Patents
Washington, DC 20231

September 3, 2002

Sir:

In reply to the Examiner's Office Action dated June 3, 2002, the following amendments and remarks are respectfully submitted in connection with the above-identified application.

IN THE DRAWINGS

Please amend Figure 3 as indicated in the proposed drawing correction being filed concurrently herewith.

IN THE SPECIFICATION:

Please replace the paragraph beginning on page 3, line 13, with the following rewritten paragraph:

A: --The etch module 42 etches the substrate, using an etchant, to provide a desired pattern on the TFT. The etchant is made from a mixture of MEA (mono ethanol acetone), BDG (butyl-di-glycol) and NMP (n-methyl-pyrrolidone).--